



O.I.P.E.		PATENT DATE	
SCANNED	Am	Q.A.	DMW

APPLICATION NO. 09/618550	CONT/PRIOR D.F.	CLASS 355	SUBCLASS 55	ART UNIT 285.1	EXAMINER H. Nguyen
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TITLE

Tetsuo Taniguchi
R. O. D. 1981

Exposure method and lithography system, exposure apparatus and method of making the apparatus, and method of manufacturing device

PTO-2040
12/88

ISSUING CLASSIFICATION												
ORIGINAL				CROSS REFERENCE(S)								
CLASS		SUBCLASS		CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)							
INTERNATIONAL CLASSIFICATION												

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	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims
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